

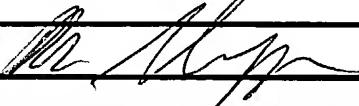
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Substitute for FORM P-1A/USPTO				<b>Complete if Known</b>	
				Application Number	10/781,844
				Filing Date	February 20, 2004
				First Named Inventor	Haruhiko KOMORIYA
				Art Unit	1621
				Examiner Name	Unassigned
Sheet	1	of	1	Attorney Docket Number	038788.53289US

<b>U.S. PATENT DOCUMENTS</b>						
Examiner Initials <sup>1</sup>	Cite No. <sup>1</sup>	Document Number		Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number-Kind Code <sup>3</sup> (if known)				
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<b>FOREIGN PATENT DOCUMENTS</b>							
Examiner Initials <sup>1</sup>	Cite No. <sup>1</sup>	Foreign Patent Document		Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T <sup>6</sup>
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<b>NON PATENT LITERATURE DOCUMENTS</b>						
Examiner Initials <sup>1</sup>	Cite No. <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.				T <sup>2</sup>
	AA	THEODORE H. FEDYNSHYN ET AL., "Fluoroaromatic Resists for 157-nm Lithography", Journal of Photopolymer Science and Technology, 2002, pp.655-666, Vol. 15, No. 4				
	AB	RALPH R. DAMMEL ET AL., "New Resin Systems for 157 nm Lithography", Journal of Photopolymer Science and Technology, 2001, pp. 603-612, Vol. 14, No. 4				

Examiner Signature		Date Considered	9/10/04
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**EXAMINER:** Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. 1 Applicant's unique citation designation number (optional). 2 See Kinds Codes of USPTO Patent Documents at [www.uspto.gov](http://www.uspto.gov) or MPEP 901.04. 3 Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). 4 For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. 5 Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST.16 if possible. 6 Applicant is to place a check mark here if English language Translation is attached.

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